REMARKS

Claims 1-14 were pending in the present application. Claims 1-5 and 8-12 were rejected, and claims 6, 7, 13, and 14 were objected to. Claims 1 and 8 are amended. No new matter is added. The rejections are respectfully traversed in light of the following remarks, and reconsideration is requested.

Rejections under 35 U.S.C. § 103

Claim 1-5 and 8-12 were rejected as being unpatentable over U.S. Publication No. 2002/0145684 to Watanabe et al (hereinafter Watanabe) in view of U.S. Patent No. 6,243,062 to Den Boer et al. (hereinafter Den Boer)

In rejecting the claims, the Examiner writes in part that Watanabe discloses "a first gate line (51) including a first input electrode (64a)" and "a pixel electrode (66) including a first contact electrode (64b)".

Applicants submit that Watanabe clearly teaches that metal films 64a, 64b are formed as separate layers and through separate process steps (Watanabe, para. [0075], FIG. 7(e)) from scanning lines 51 (Watanabe, para. [0071], FIG. 6(b)) and pixel electrode 66 (Watanabe, para. [0077], FIG. 7(g)). Accordingly, scanning lines 51 and pixel electrode 66 do not "include" metal films 64a and 64b, respectively, as alleged by the Examiner.

Furthermore, the Examiner writes in part that it is well known in the art to form double-layered (or multi-layered) gate lines for the benefit of preventing corrosion. However, the Examiner points to no reference for such a showing of the redundant gate lines in proper configuration as taught in the present invention or the motivation to combine such elements.

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Furthermore, Watanabe clearly shows that insulating films 63 cover scanning lines 51 (Watanabe, para. [0072], FIG. 6(c)). Accordingly, assuming arguendo that Watanabe could be combined with another reference or well known art showing a redundant gate line, an insulating film would intervene between the gate line and a redundant gate line formed on a substrate, and no gate line could be formed at least partially directly on a redundant gate line formed on an insulating substrate.

In contrast, the present invention clearly teaches a gate line 122 formed at least partially directly on a redundant gate line 142/146 (FIGS. 2, 3 and 8, 9).

In particular, Claim 1 recites "first and second redundant gate lines . . . ; first and second floating electrodes made of an opaque conductor, formed on the insulating substrate, and disposed between the first and second redundant gate lines; . . . a first gate line formed at least partially directly on the first redundant gate line and including a first input electrode . . . ; a second gate line formed at least partially directly on the second redundant gate line and including a second input electrode . . . ; and a pixel electrode including a first contact electrode overlapping the first floating electrode," in addition to other limitations.

Claim 8 similarly recites "first redundant gate lines including a first input electrode . . . ; second redundant gate lines including a second input electrode . . . ; a first gate line formed at least partially directly on the first redundant gate line; a second gate line formed at least partially directly on the second redundant gate line," in addition to other limitations.

Accordingly, because Watanabe in view of Den Boer does not disclose or suggest all the limitations of Claims 1 and 8, Claims 1 and 8 are patentable over Watanabe in view of Den Boer.

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Claims 2-5 and 9-12 are dependent upon Claims 1 and 8, and contain additional limitations that further distinguish them from the cited references. Therefore, Claims 2-5 and 9-12 are allowable over Watanabe in view of Den Boer for at least the same reasons provided above for Claims 1 and 8, respectively.

Accordingly, Applicants respectfully request reconsideration and withdrawal of the rejections under 35 U.S.C. § 103.

Allowable Subject Matter

Applicants wish to thank the Examiner for the indication that Claims 6, 7, 13, and 14 would be allowable if rewritten in independent form including all of the limitations of the based claim and any intervening claims.

Claims 6-7 and 13-14 are dependent upon Claims 1 and 8, and contain additional limitations that further distinguish them from the cited references. Therefore, Claims 6-7 and 13-14 are allowable over the cited references for at least the same reasons provided above for Claims 1 and 8, respectively.

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CONCLUSION

For the foregoing reasons, Applicants believe pending claims 1-14 are allowable, and a notice of allowance is respectfully requested. If the Examiner has any questions regarding the application, the Examiner is invited to call the undersigned Attorney at (949) 752-7040.

Certificate of Transmission

Certificate of Transmission: I hereby certify that this correspondence is being transmitted to the United States Patent and Trademark Office (USPTO) via the USPTO's electronic filing system on the date below.

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Respectfully submitted,

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